

# **ENEE 359a**

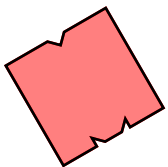
## ***Digital VLSI Design***

### ***CMOS Memories and Systems: Part II, DRAM Circuits***

**Prof. Bruce Jacob**  
**blj@eng.umd.edu**

**Credit where credit is due:**

Slides contain original artwork (© Jacob 1999–2004, Wang 2003/4) as well as material taken from Keeth & Baker's DRAM Circuit Design.



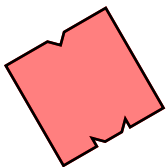
# Overview

## DRAM:

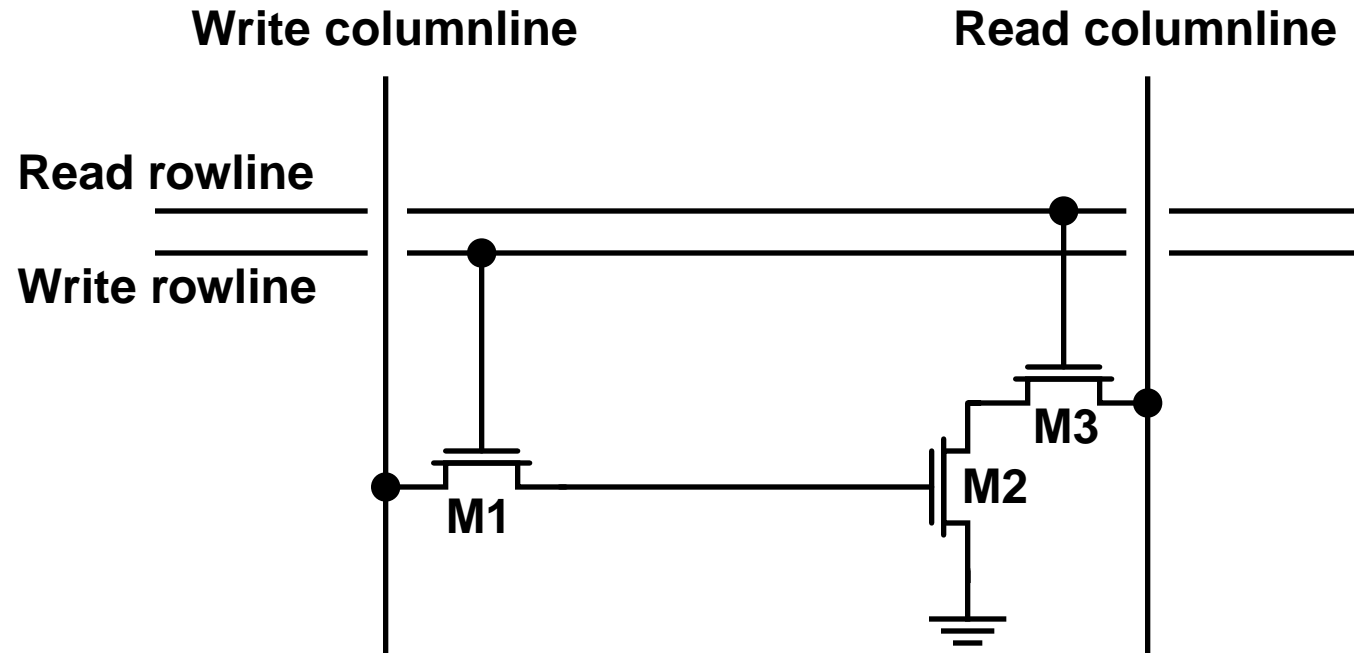
- **DRAM systems**
- **DRAM circuits**

## SRAM:

- **SRAM systems**
- **SRAM circuits**
- **Register files**

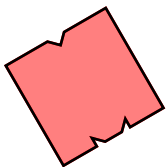


# The Original 3T DRAM Cell



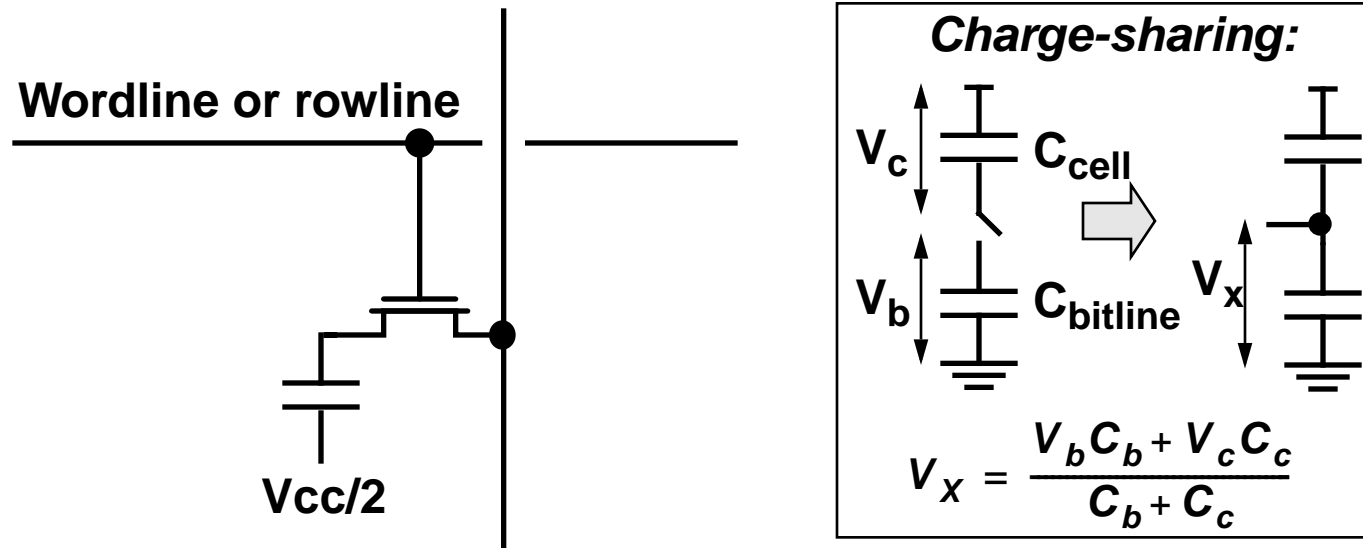
## First generation DRAM cell

- **MOSFET #2 is used as storage node (obvious to see why “dynamic”)**
- **Read columnline precharged for read; line either pulled to GND or not.**

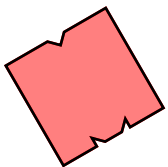


# Second Generation 1T1C Cell

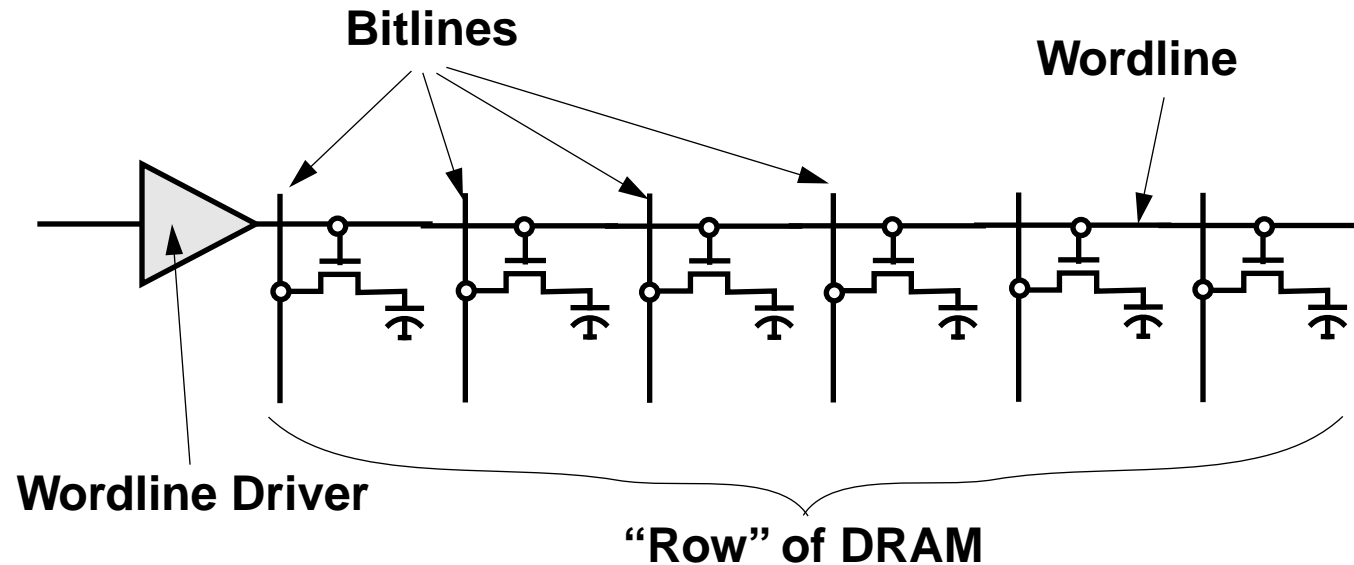
Digitline, columnline, or bitline



- **Wordline can be polysilicon; MOSFET formed by wordline over n+ active area**
- **To write full  $V_{cc}$  to storage capacitor, rowline (gate) must be driven to voltage  $V_{ccp} > V_{cc} + V_{th}$**
- **Bitline can be metal or polysilicon**
- **Charge-sharing: what potential should be at other side of storage capacitor? (e.g.  $V_0 = 0, V_1 = V_{cc}$ )**

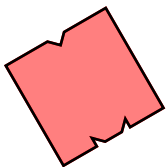


# Wordline

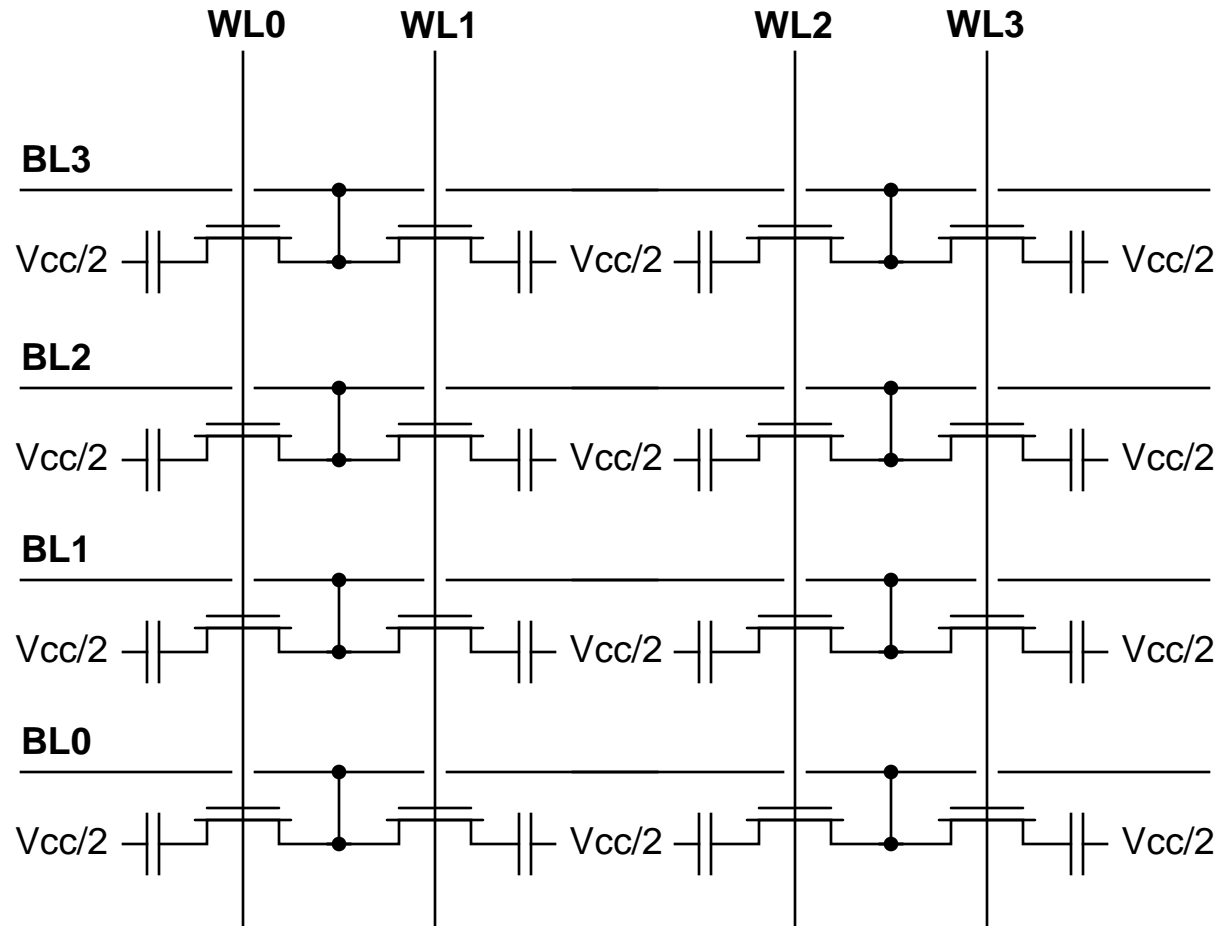


**Wordline presents large capacitive load;  
slow, limits  $t_{RC}$  (time to open & close row)**

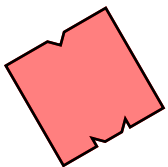
- Use wordline driver: large FETs (remember scaling?)
- Polysilicon wordline usually topped with silicide ("polycide" wordline); increases conductivity
- Additional drivers can be placed along length
- Wordline can be "stitched" with pieces of metal
- Typical organization: **512 wordlines x 512 bitlines**



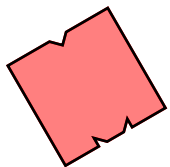
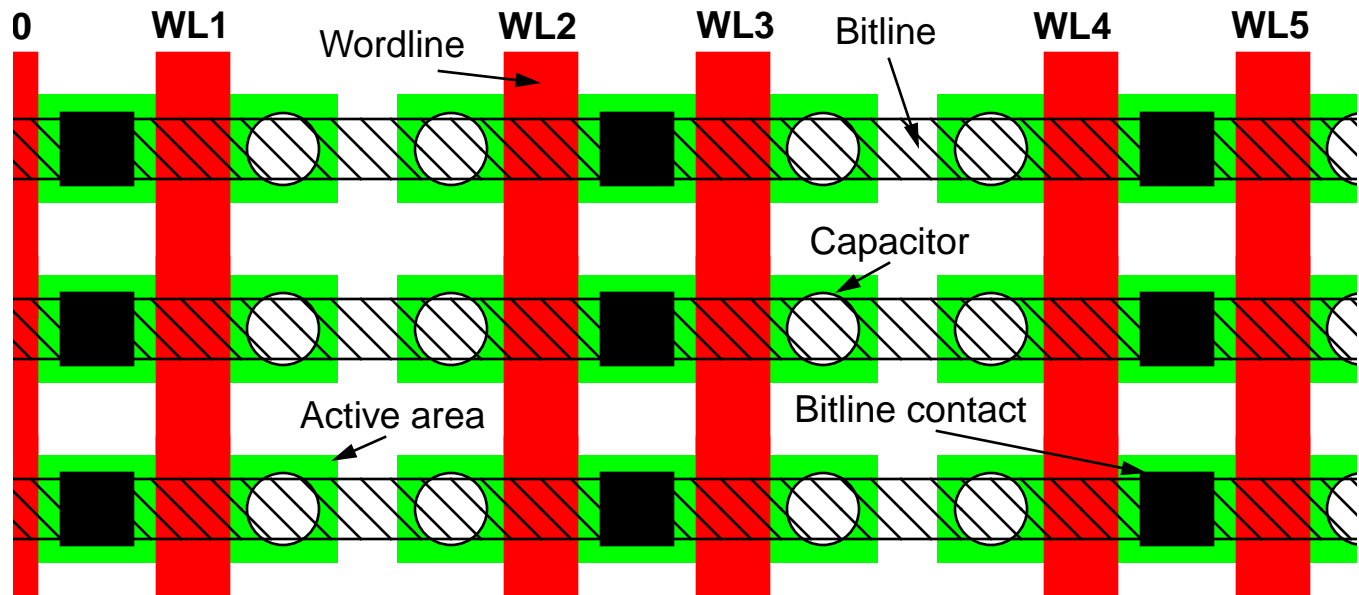
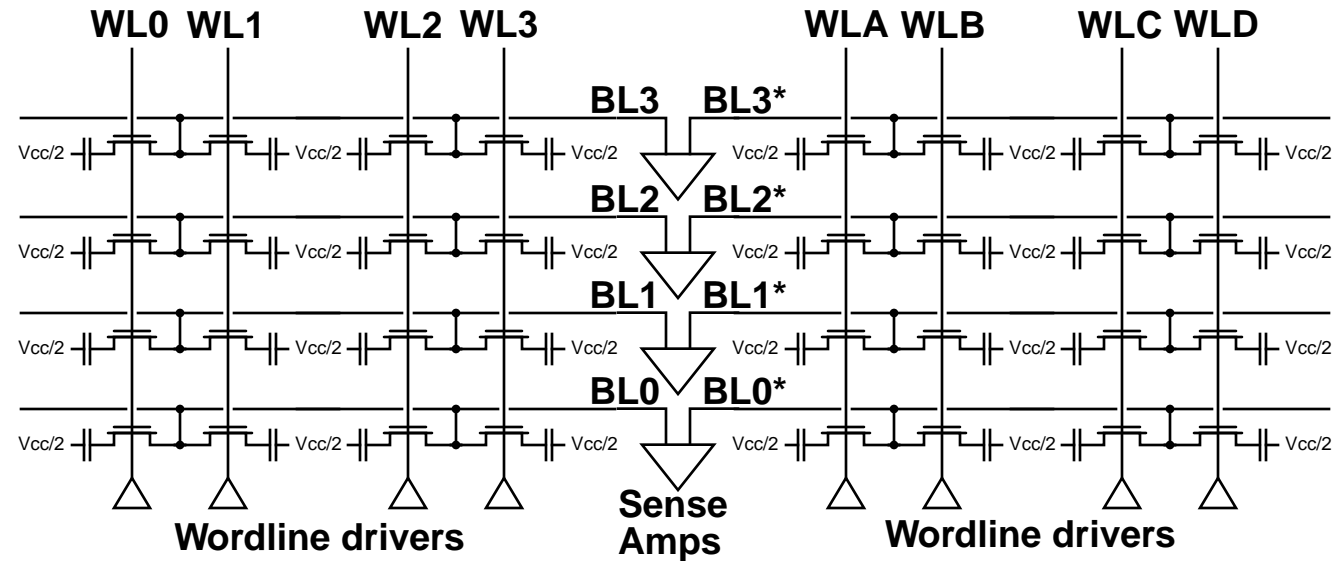
# DRAM Array: Open Bitline



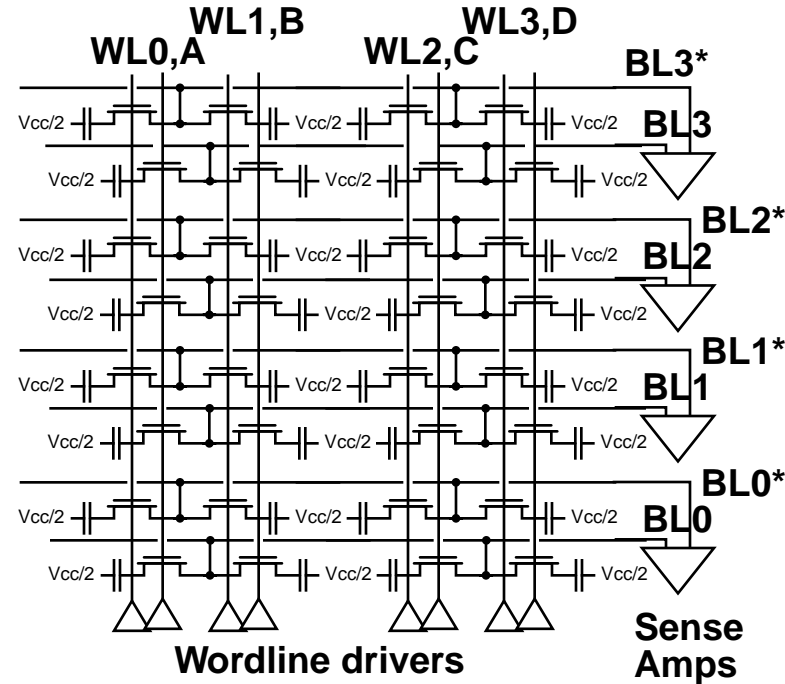
- **Adjacent cells share connection to bitline**
- **Note change in orientation (rotated 90°)**



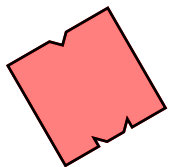
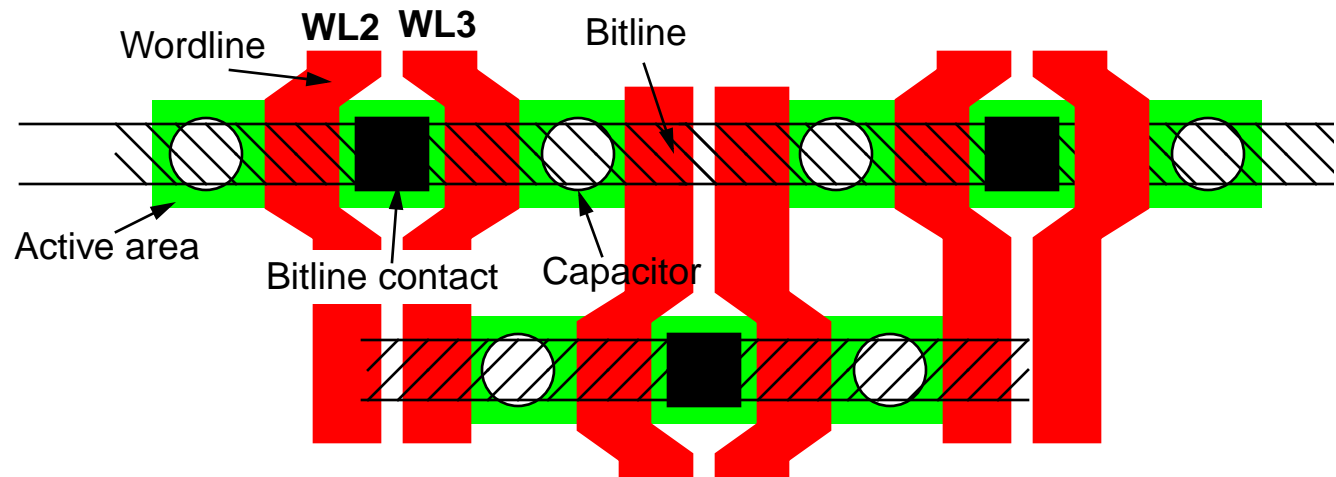
# Open Bitline Array & Cells



# Folded Bitline Array & Cell

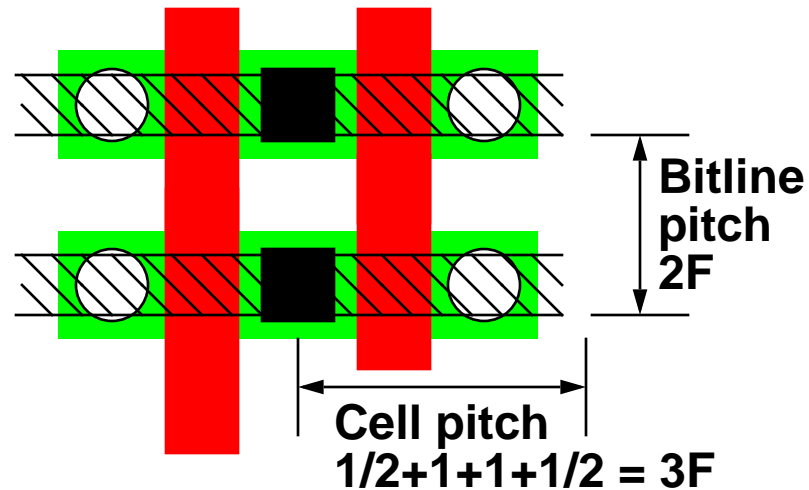


Routing BLX and BLX\* together improves noise immunity (esp. in conjunction with *bitline twisting ...*)

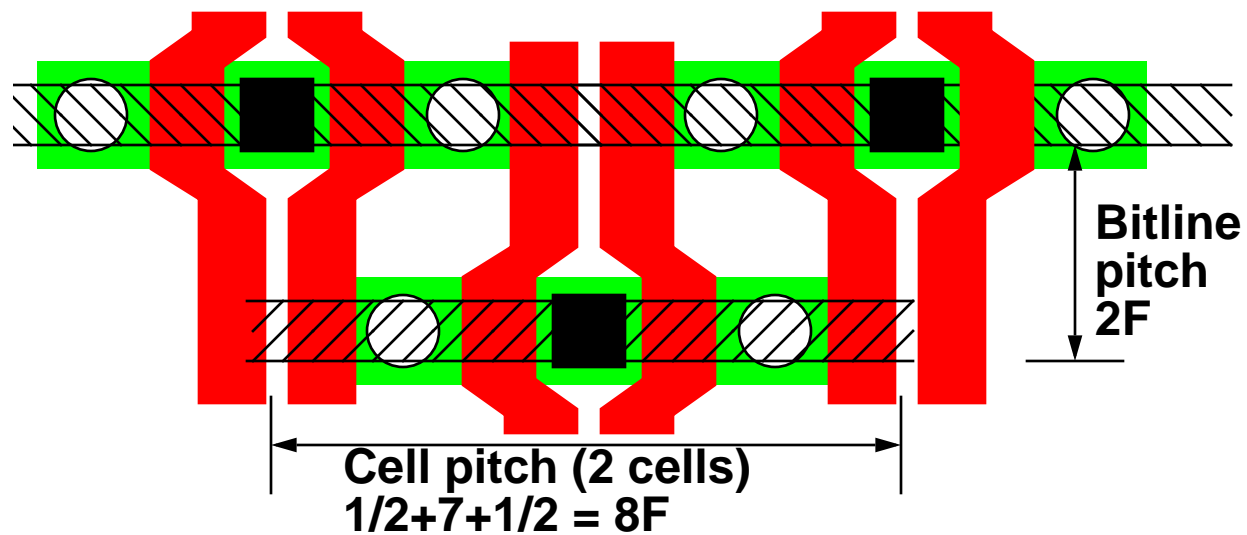




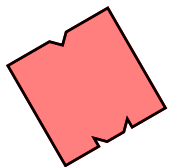
# Open vs. Folded Cell Areas



Open bitline cell:  
 $1F \times 3F = 6F^2$

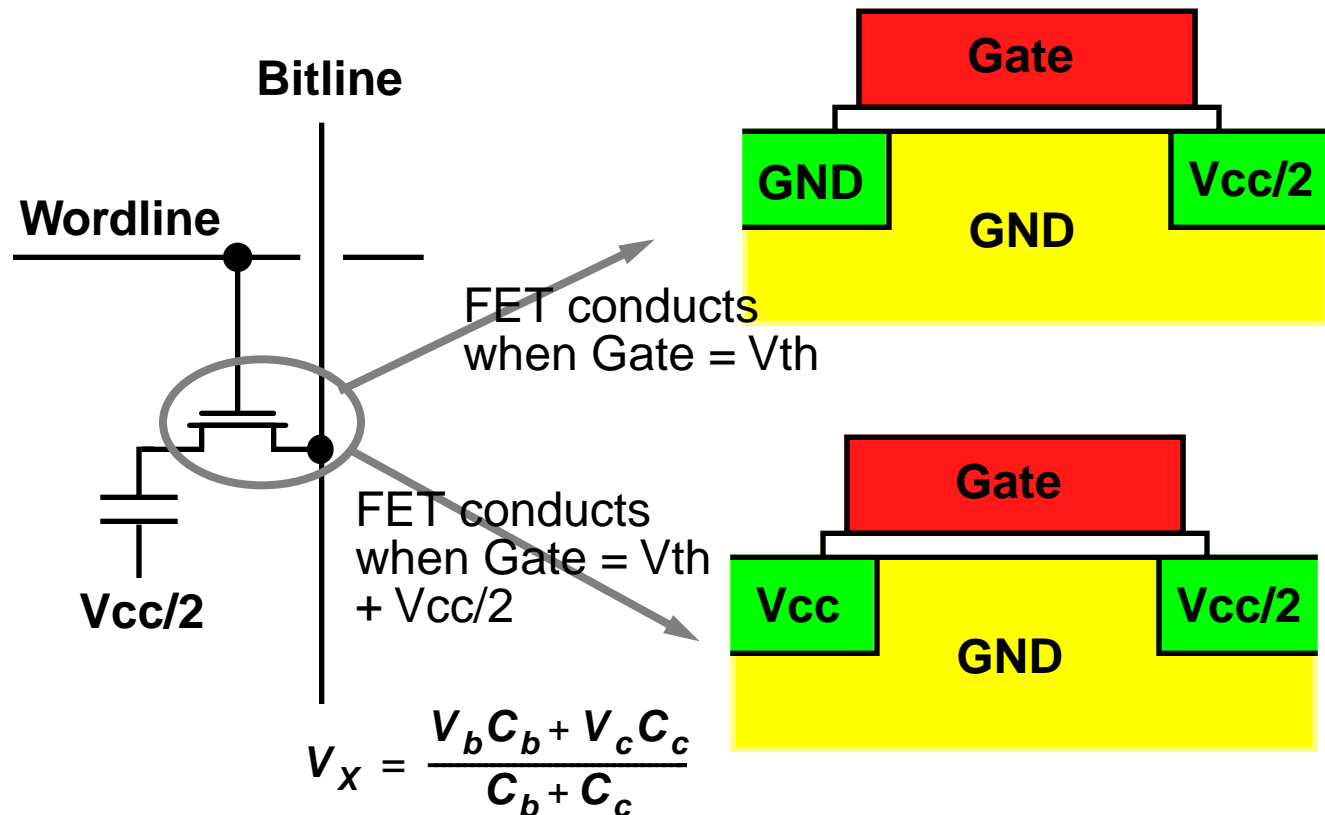


Folded bitline cell:  
 $2F \times 4F = 8F^2$

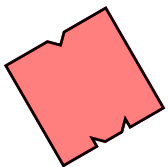


# Sensing I

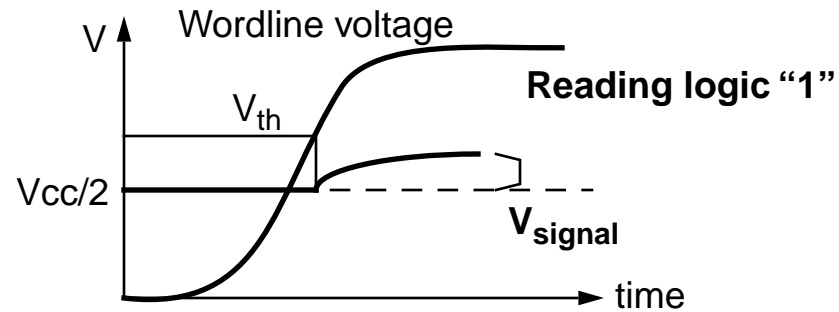
## Recall behavior of nFET:



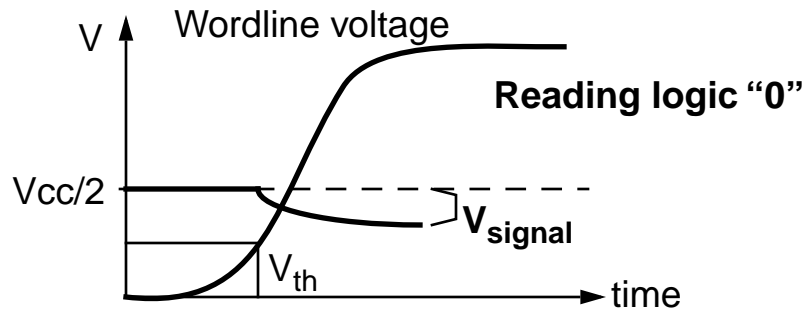
- Scenario 1: nFET conducts when gate voltage exceeds  $\min\{\text{Source, Drain}\}$  (GND) by  $V_{th}$
- Scenario 2: nFET conducts when gate voltage exceeds  $\min\{\text{Source, Drain}\}$  ( $V_{cc}/2$ ) by  $V_{th}$



# Sensing II



$$V_X = \frac{V_b C_b + V_c C_c}{C_b + C_c}$$



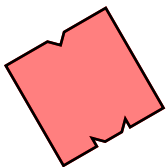
$$V_{signal} = \frac{V_c C_c}{C_b + C_c}$$

## Passing Logic 1:

- Capacitor begins to discharge when wordline exceeds bitline PRECHARGE voltage by V<sub>th</sub>

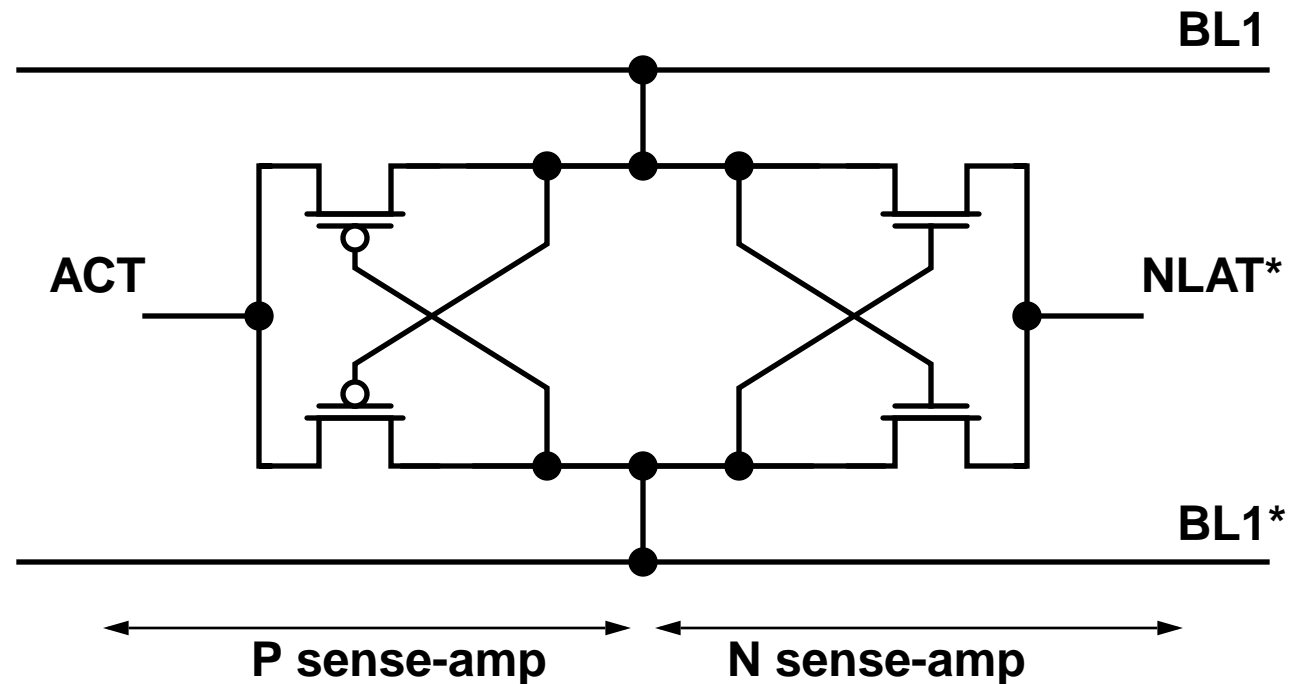
## Passing Logic 0:

- Capacitor begins to discharge when wordline exceeds V<sub>th</sub>

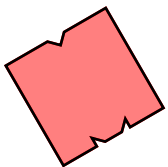


# Sense Amplifiers I

## Circuit diagram:

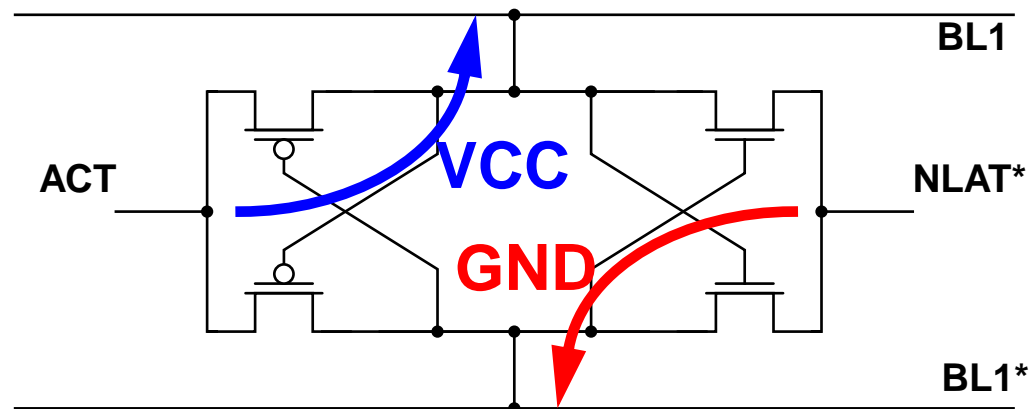


- Initially, ACT at Vss (GND) and NLAT\* held at Vcc/2 (both BL1 and BL1\* are at Vcc/2 as well)
- **To read:** Wordline pulled to Vcc+Vth, BL1/\* changes
- **To sense:** first, NLAT\* is pulled towards ground
- Then ACT is pulled towards Vcc

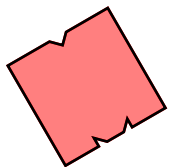
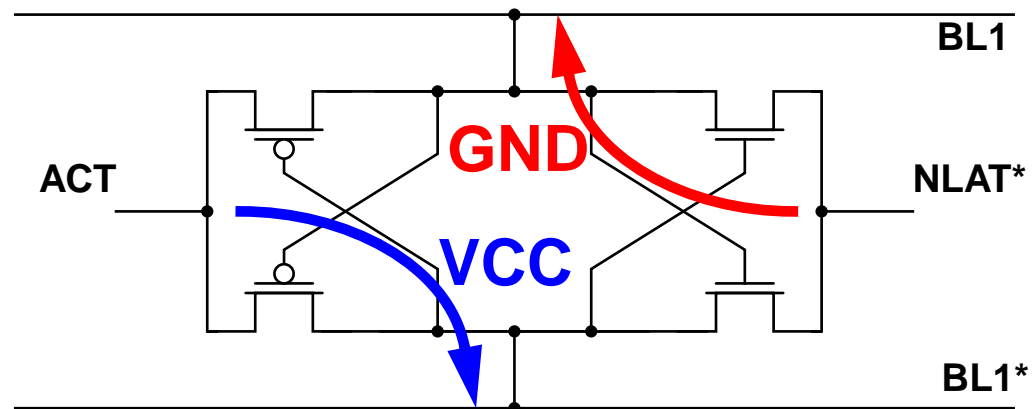


# Sense Amplifiers II

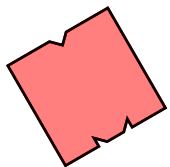
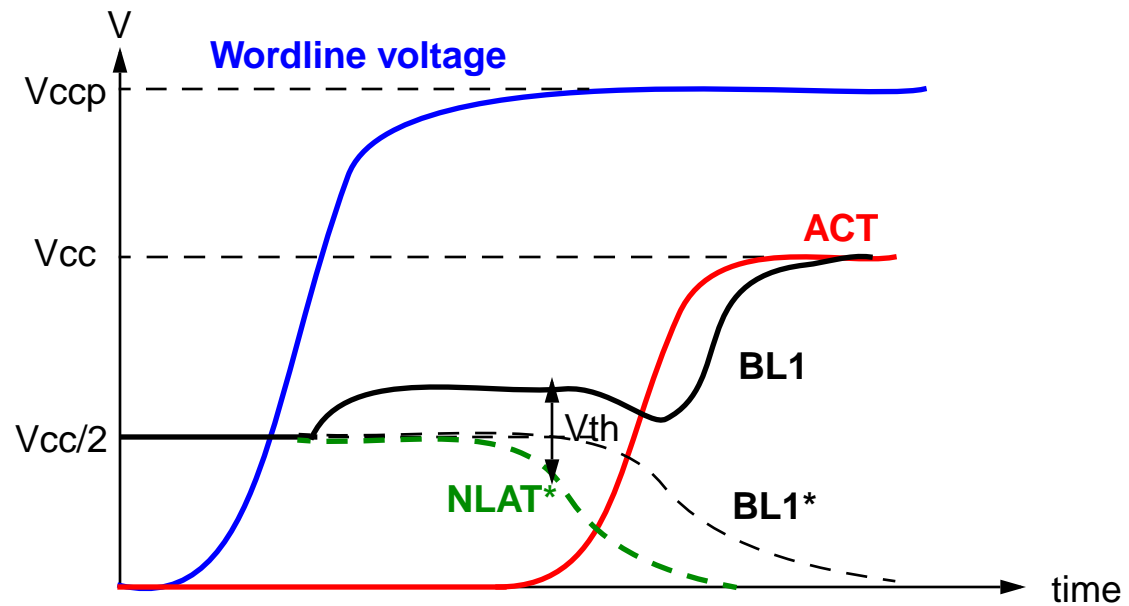
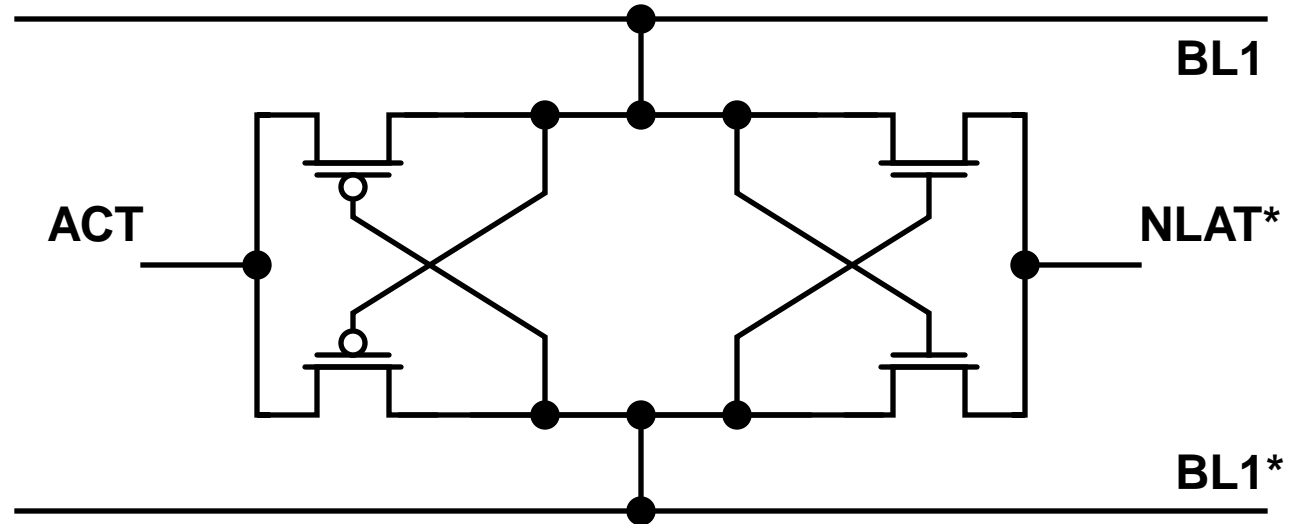
## Basic idea:



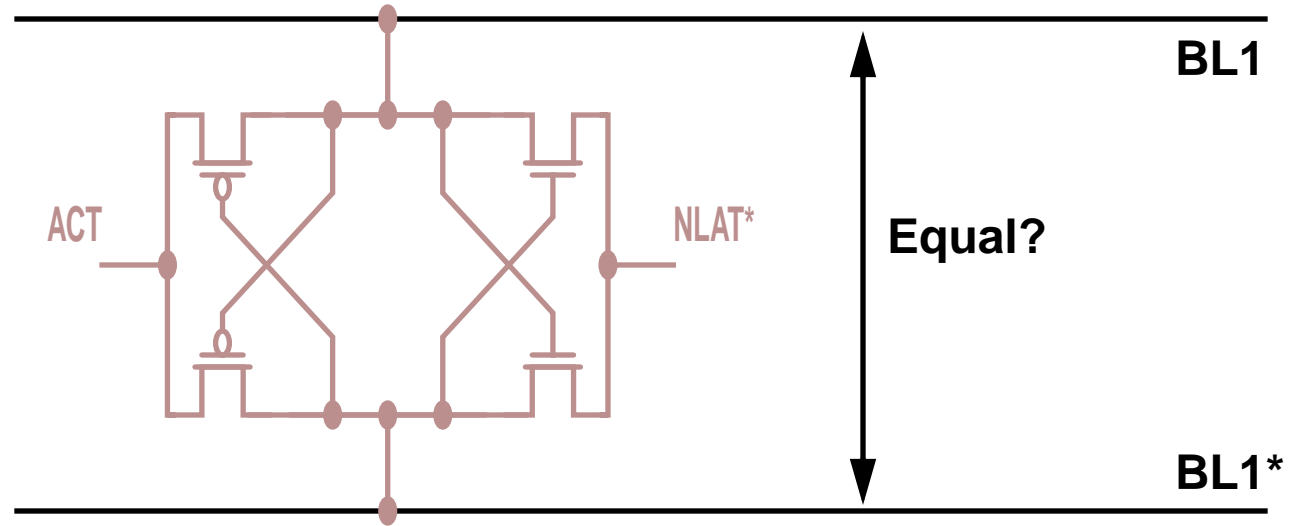
OR



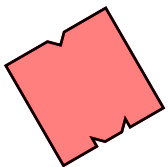
# Sense Amplifiers III



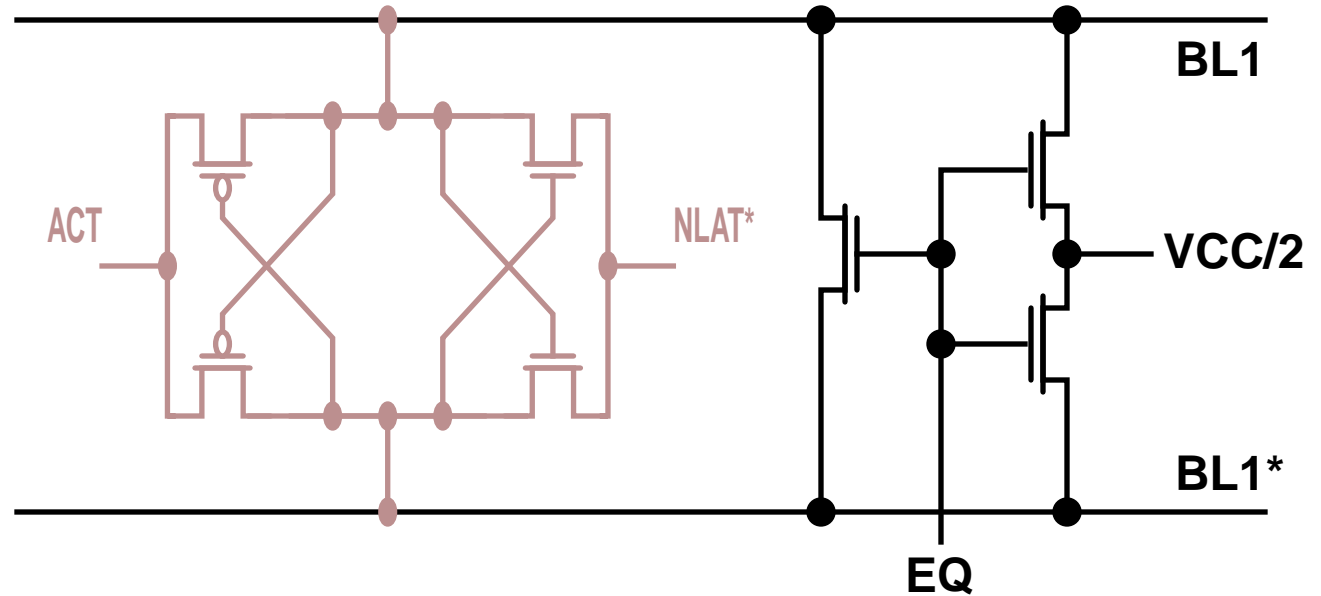
# Equilibration I



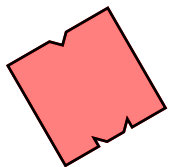
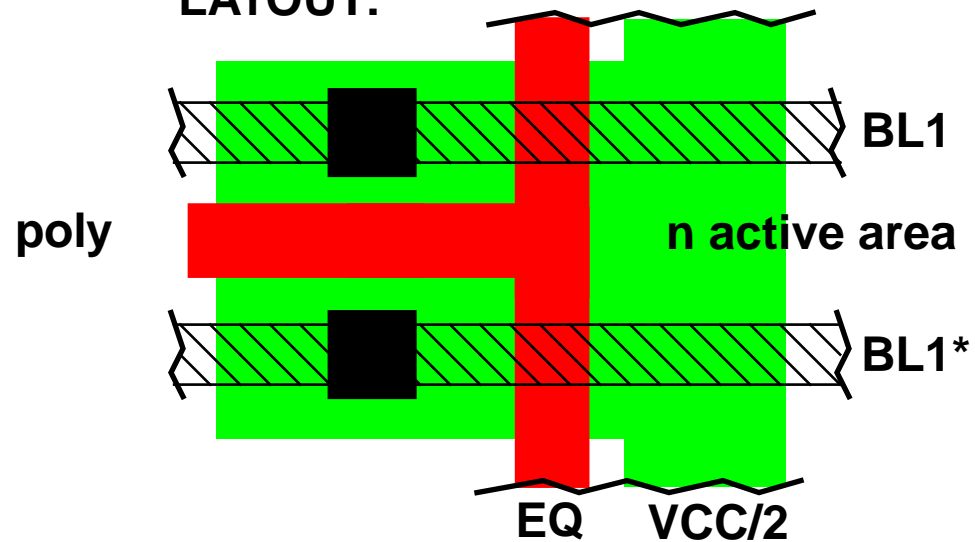
**Textbook's term: *equalization***



# Equilibration II

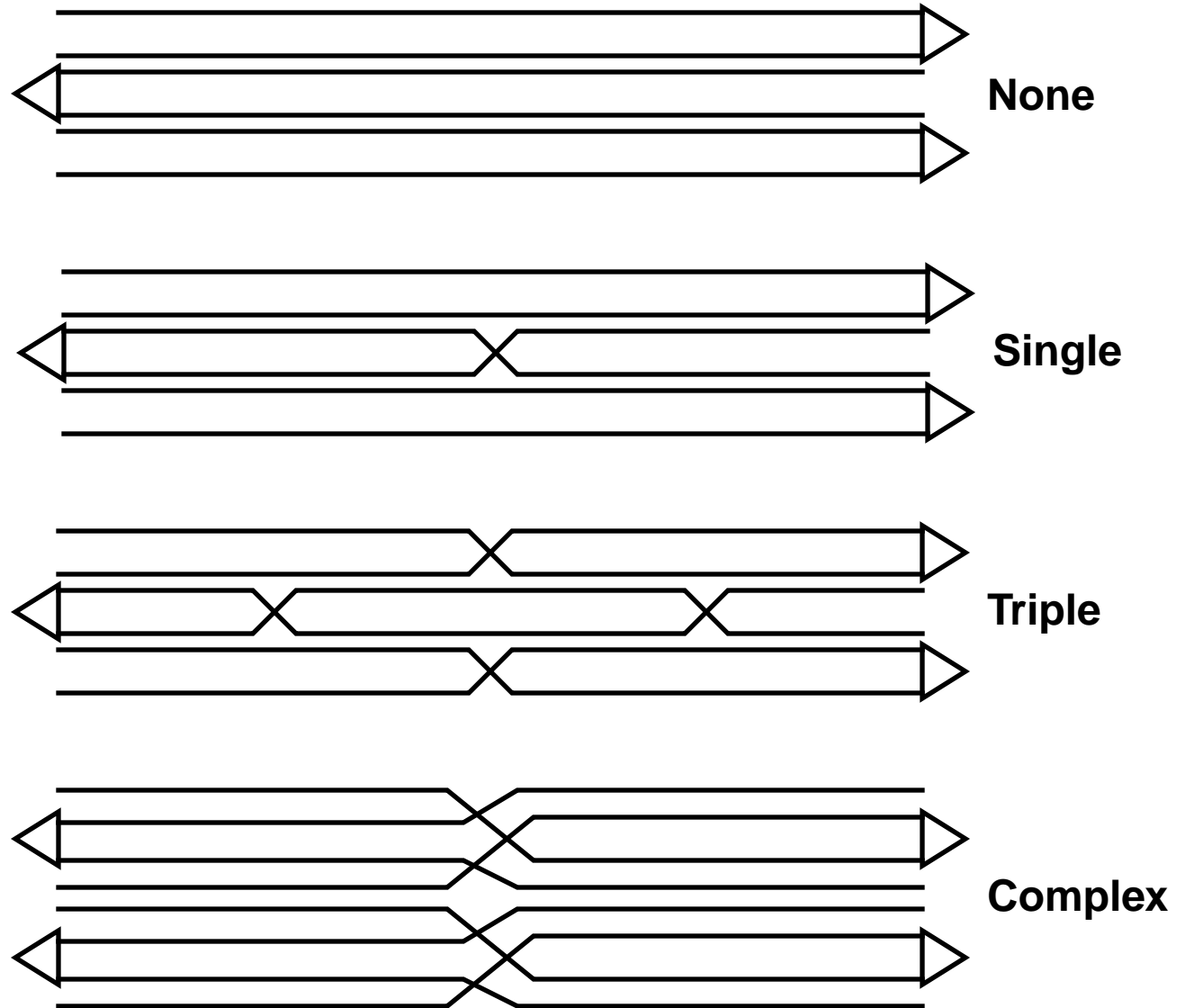


## LAYOUT:

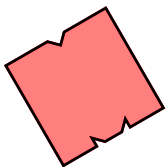




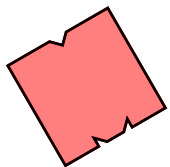
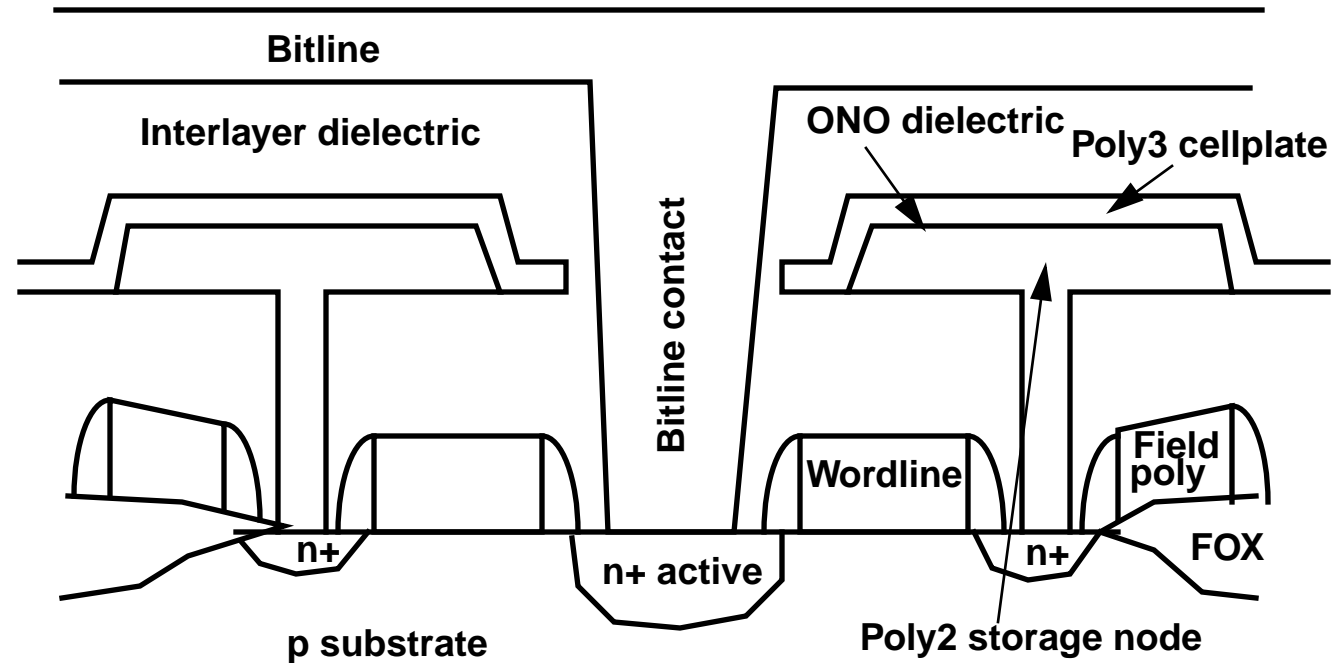
# Bitline Twisting



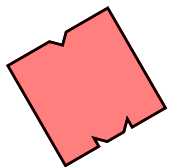
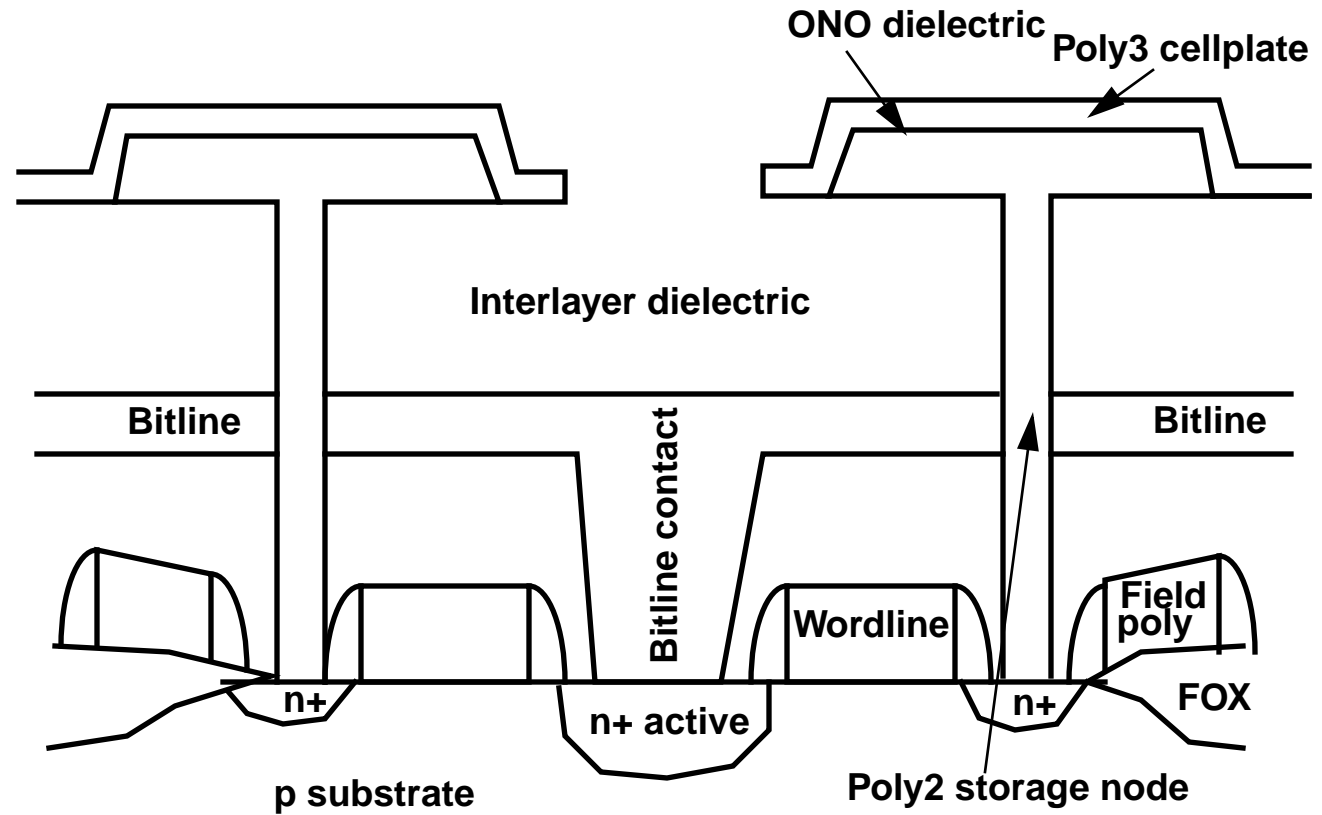
... this is just a small sample



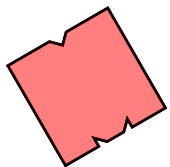
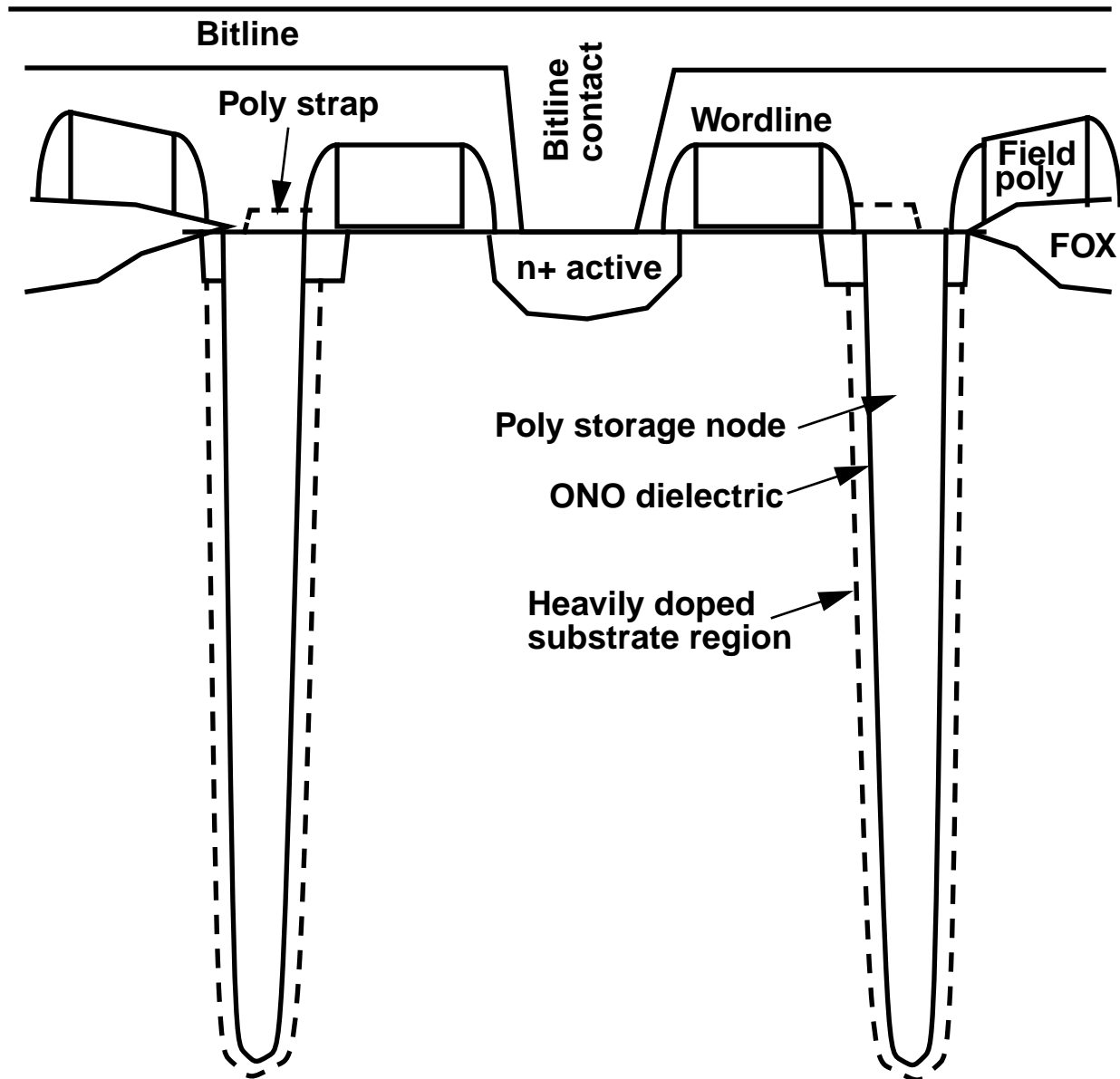
# Cells: Buried Capacitor



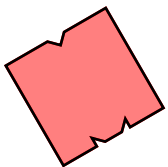
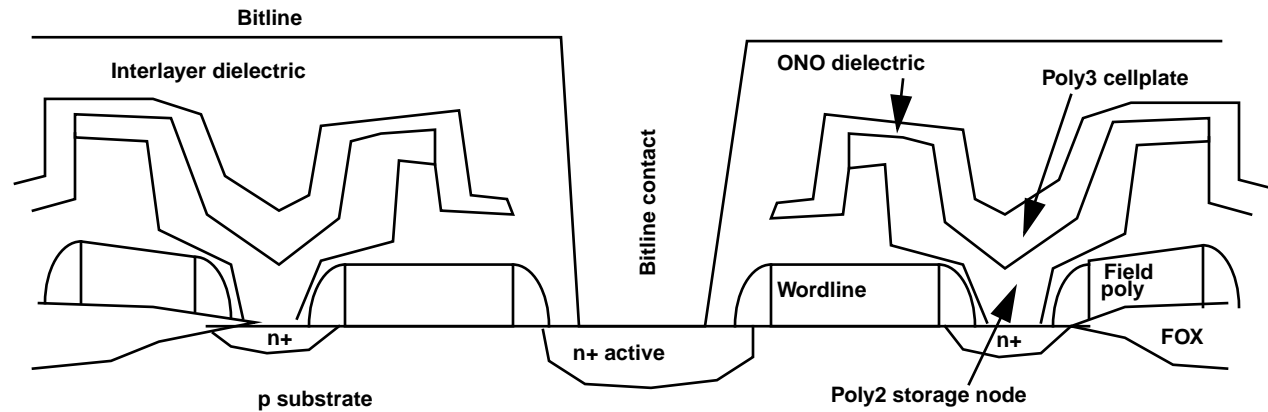
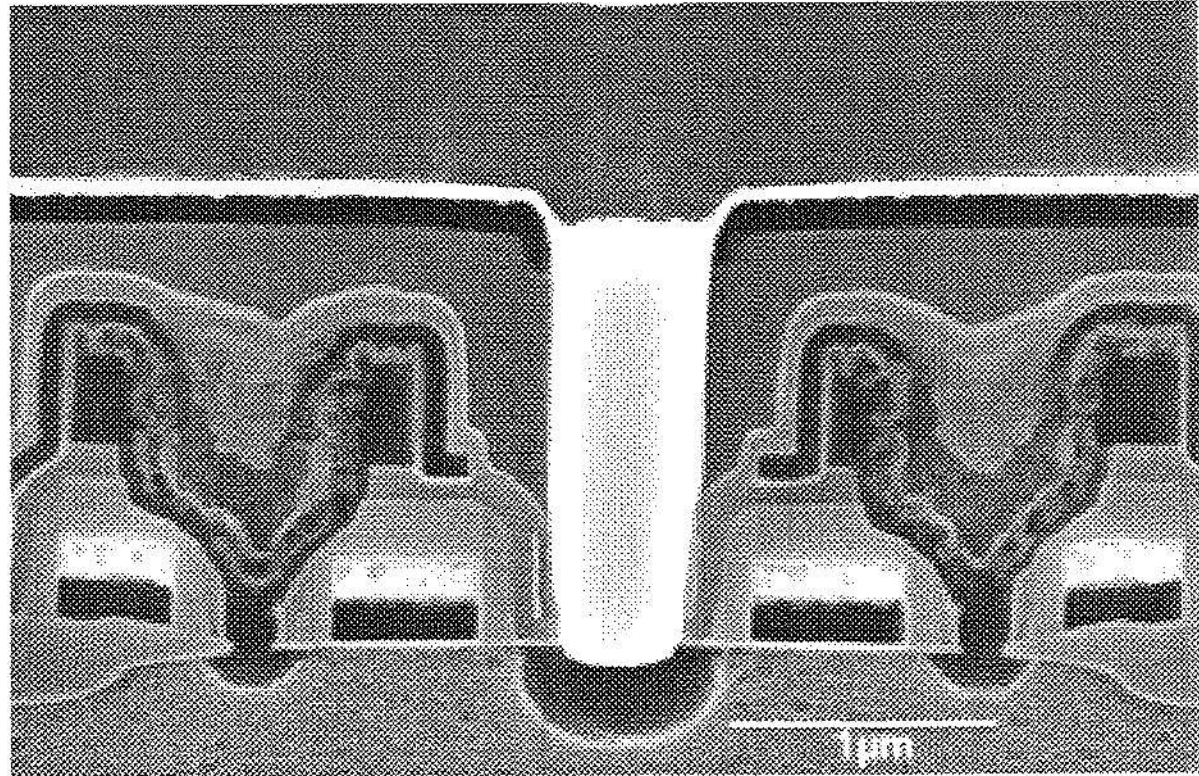
# Cells: Buried Bitline/Digitline



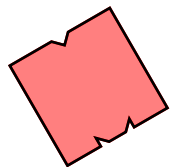
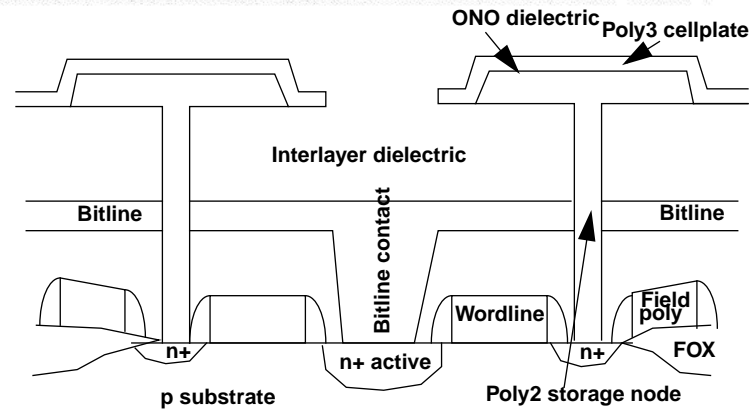
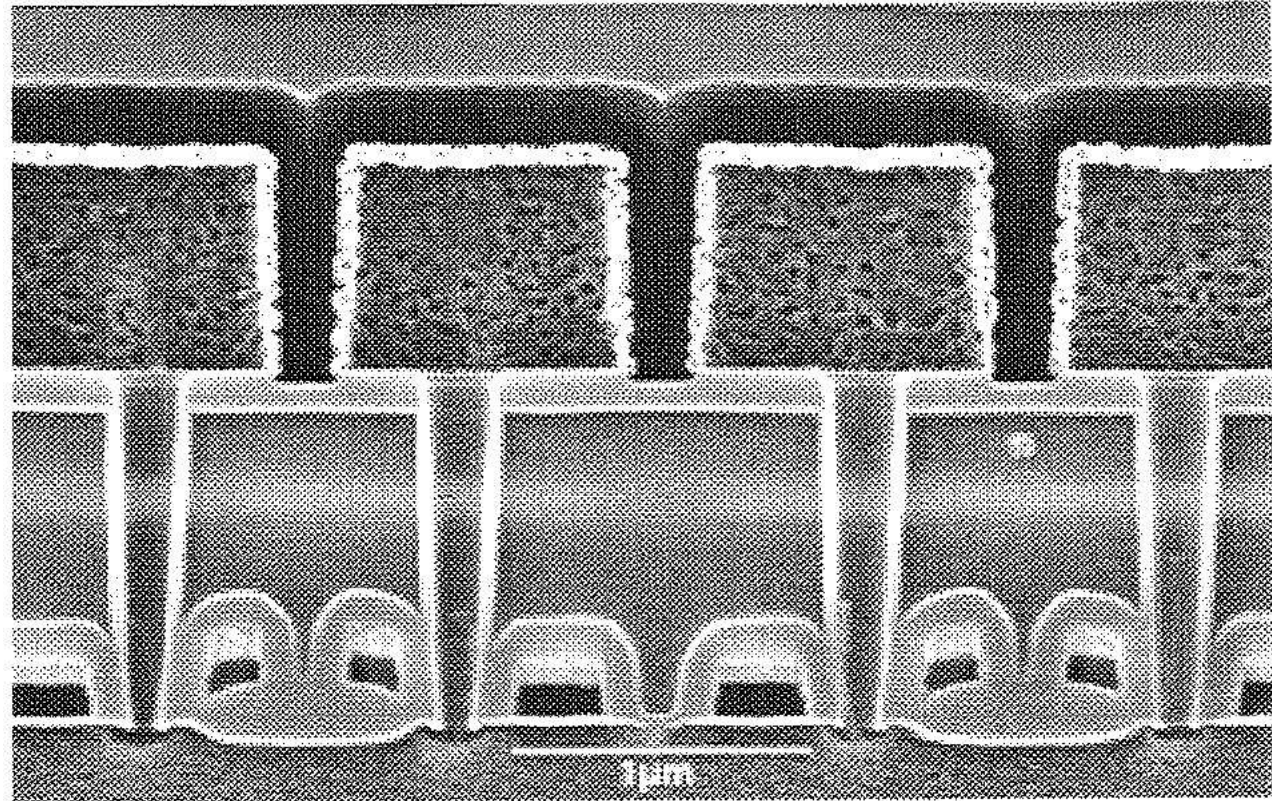
# Cells: Trench Capacitor



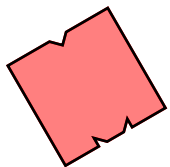
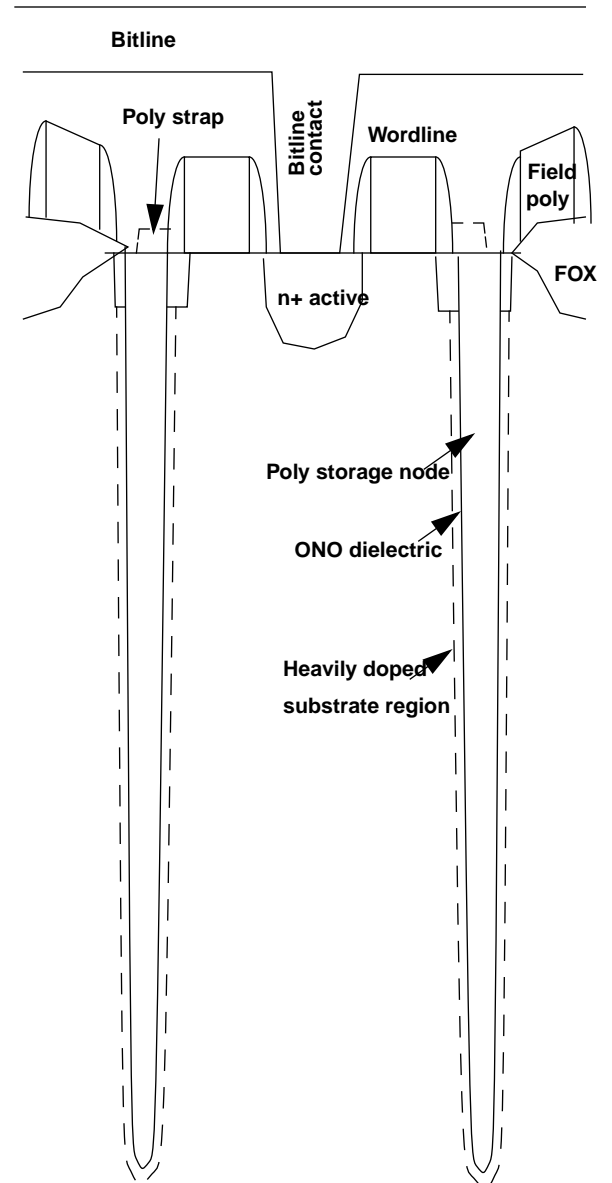
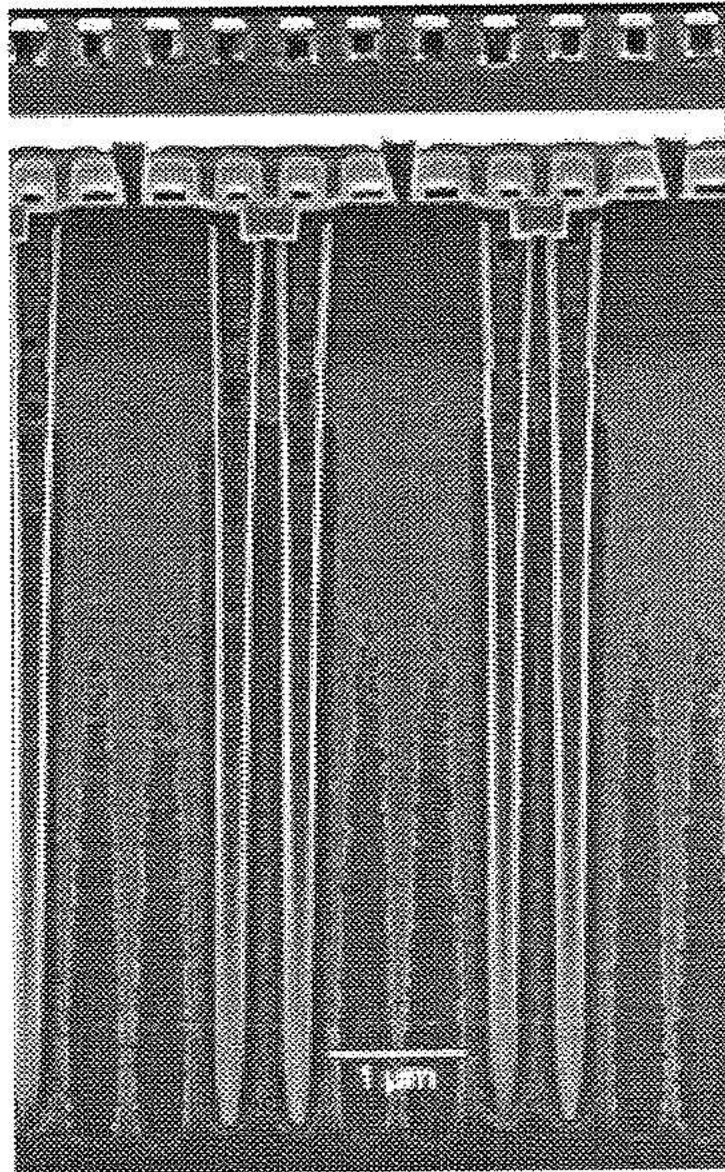
# Cells: Buried Capacitor



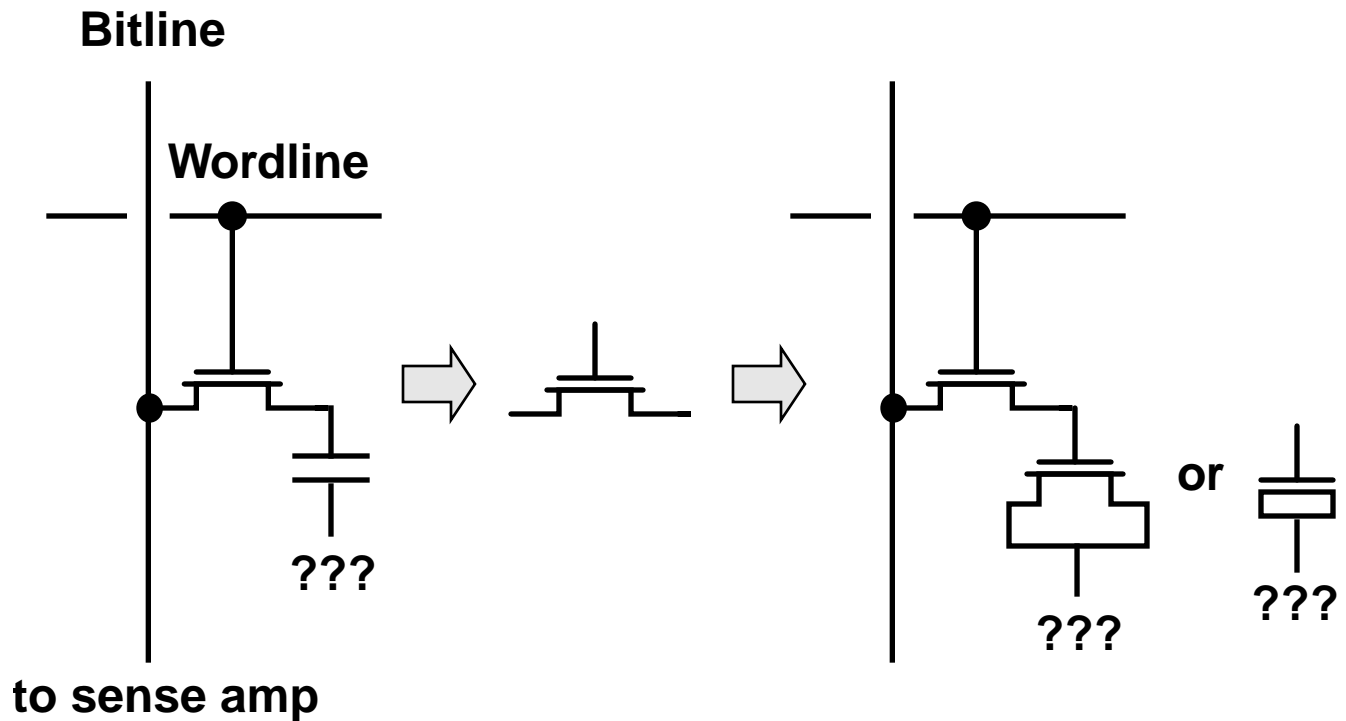
# Cells: Buried Bitline/Digitline



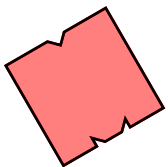
# Cells: Trench Capacitor



# Cells: eDRAM (logic process)

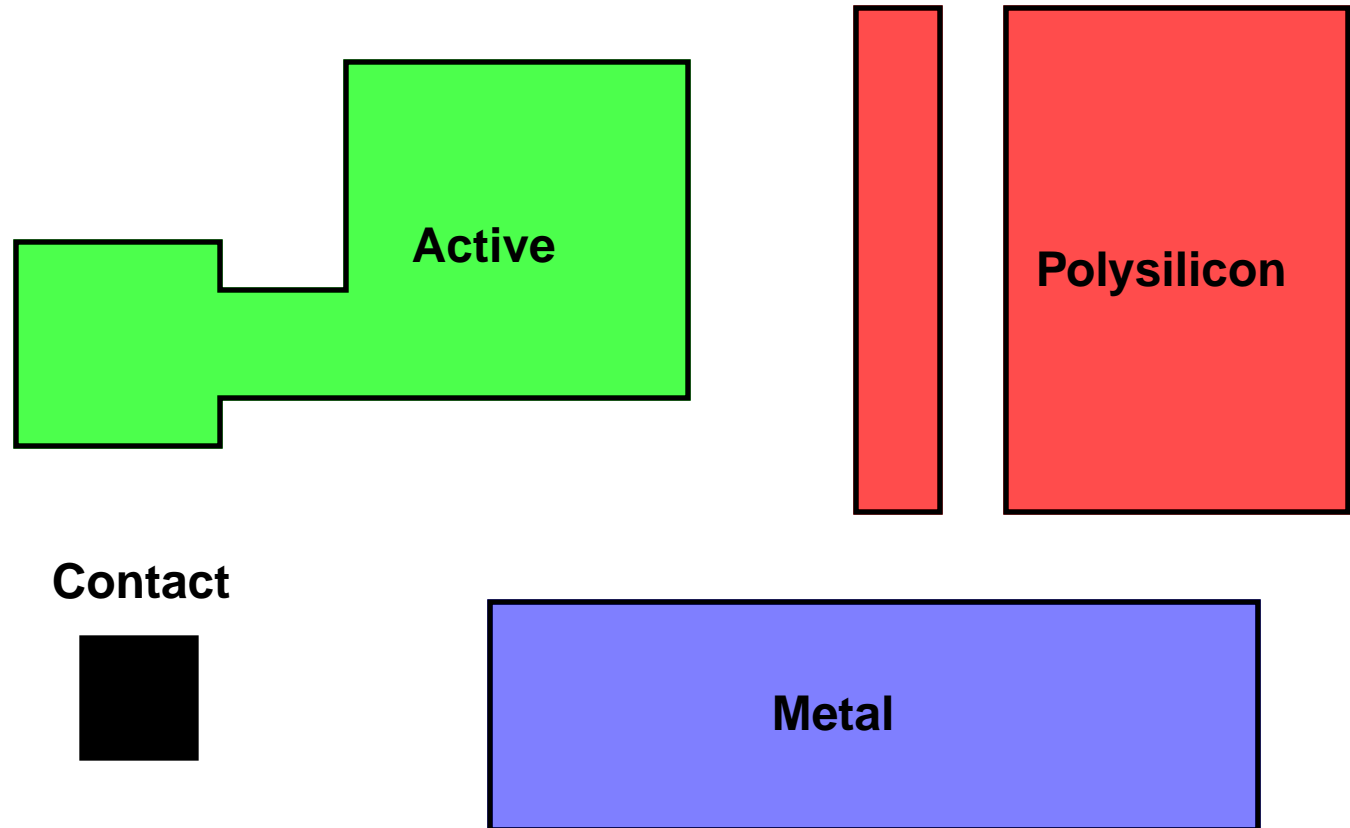


- **Basic idea: replace funky capacitor structure (which requires special process technology to produce) with something that looks like logic**
- **DRAM is now “embedded” into a logic process: on same chip as CPU cores, etc.**
- **Question: do we still tie far side to  $V_{CC}/2$ ?**

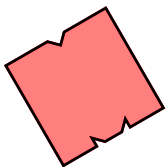




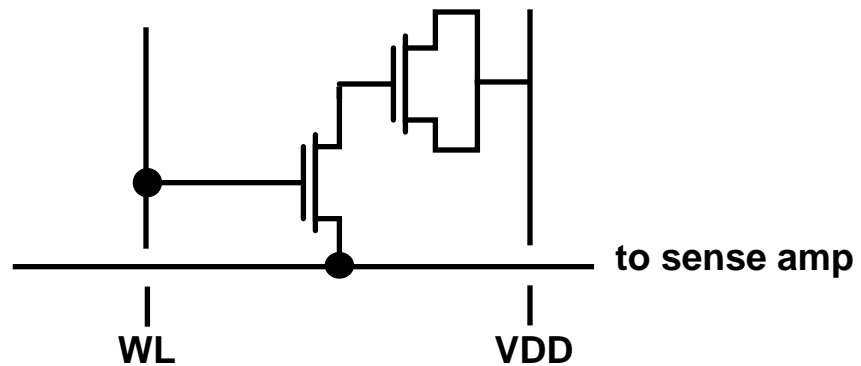
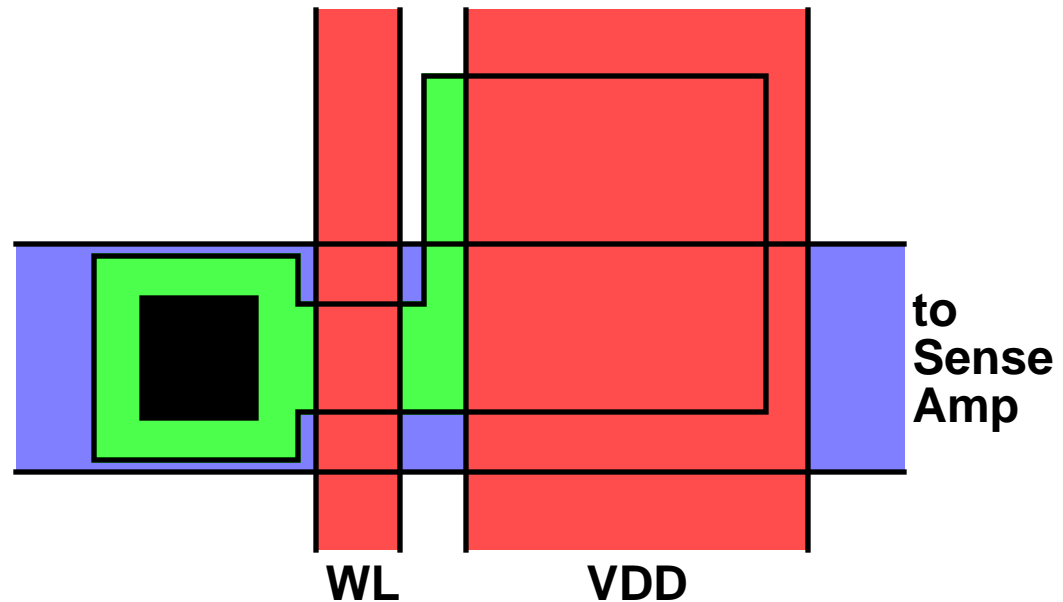
# Cells: eDRAM (logic process)



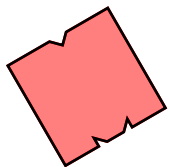
**The components**



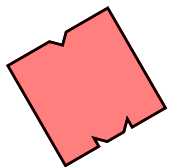
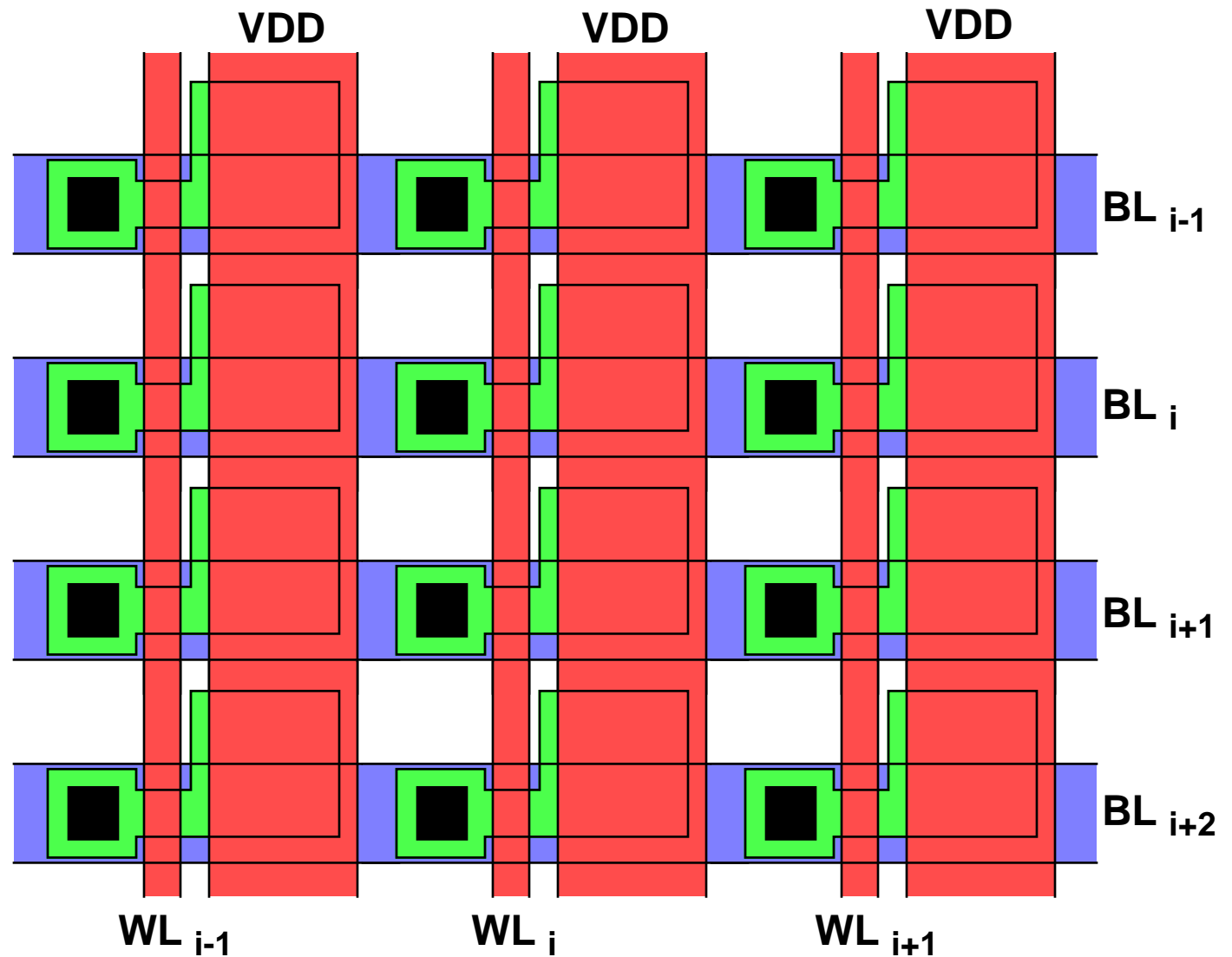
# Cells: eDRAM (logic process)



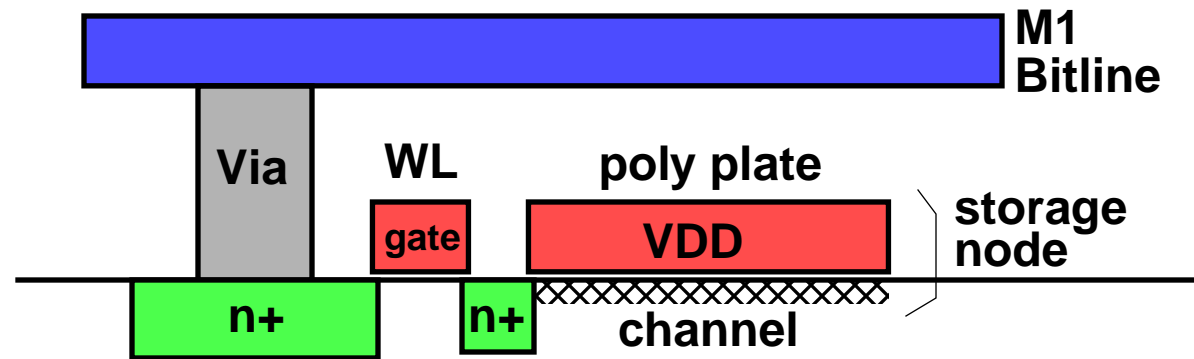
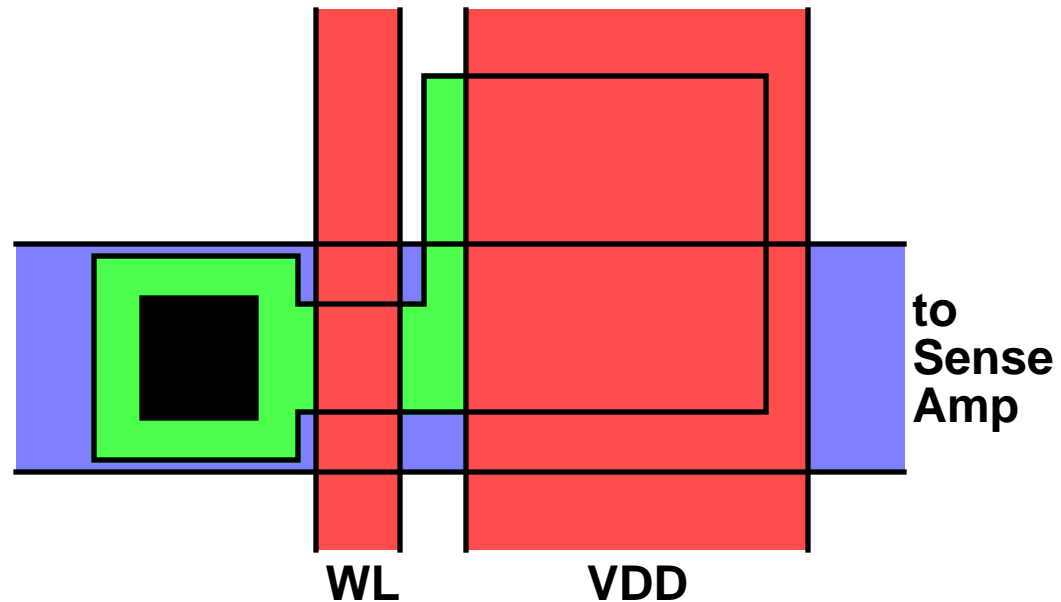
The cell



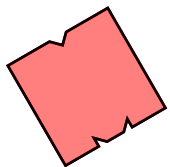
# Cells: eDRAM (logic process)



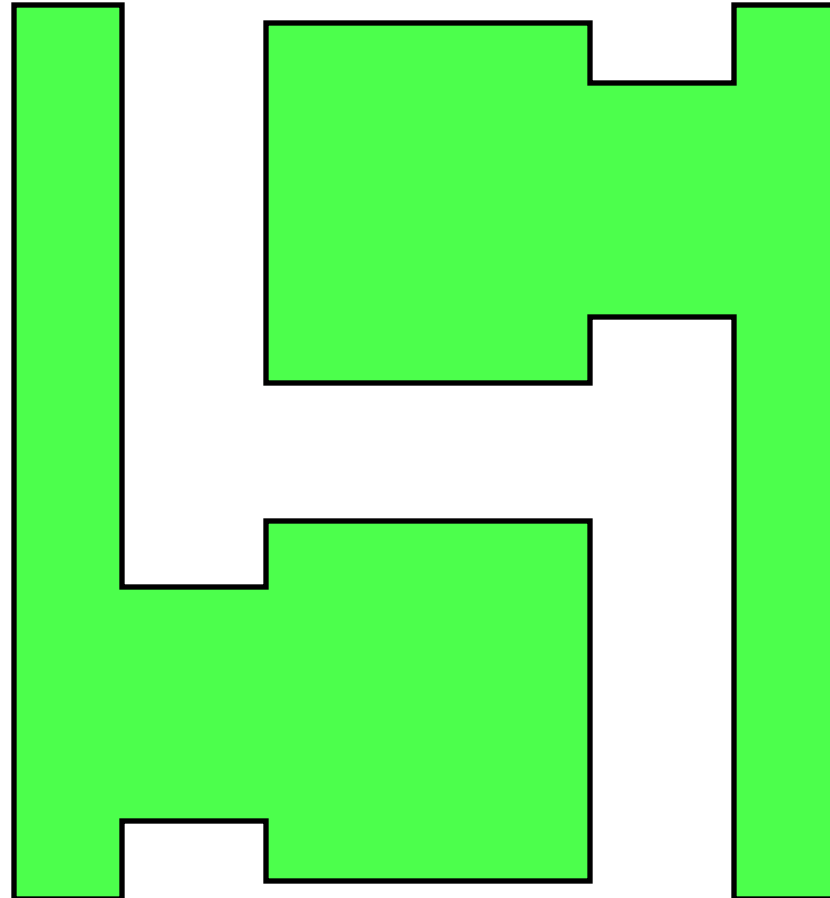
# Cells: eDRAM (logic process)



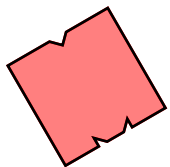
**Why is poly plate held at (global) VDD?**



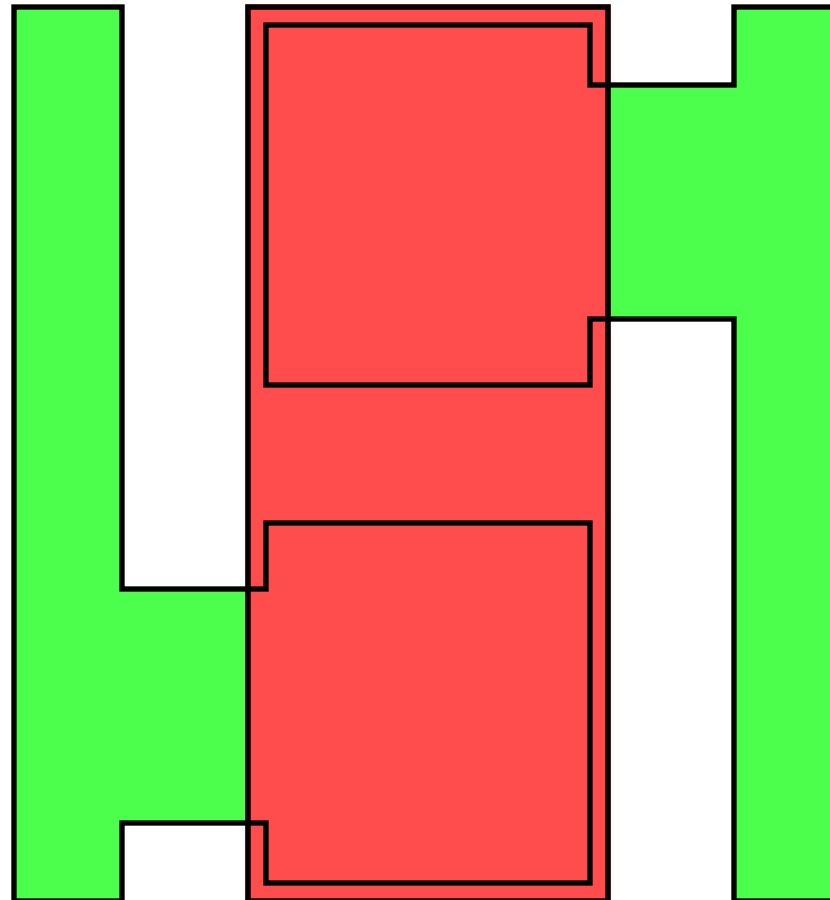
# eDRAM: 2-bit cell (CMU)



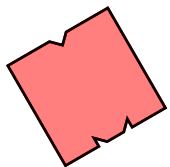
**Active area**



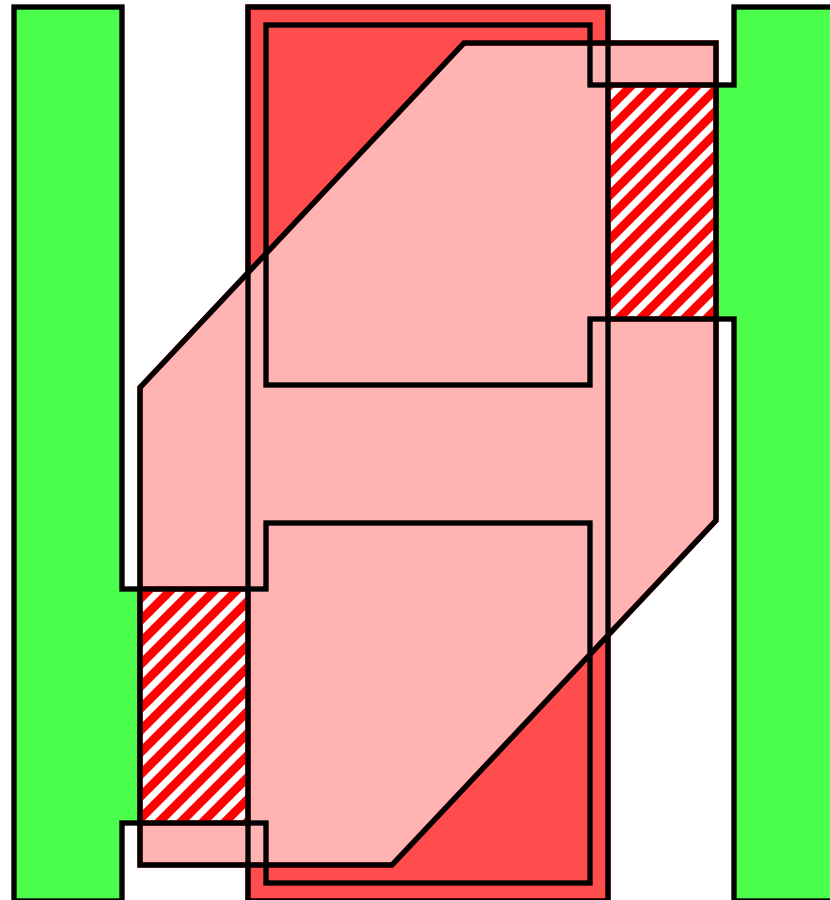
# eDRAM: 2-bit cell (CMU)



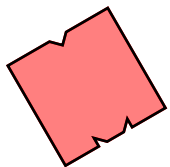
**Poly I**



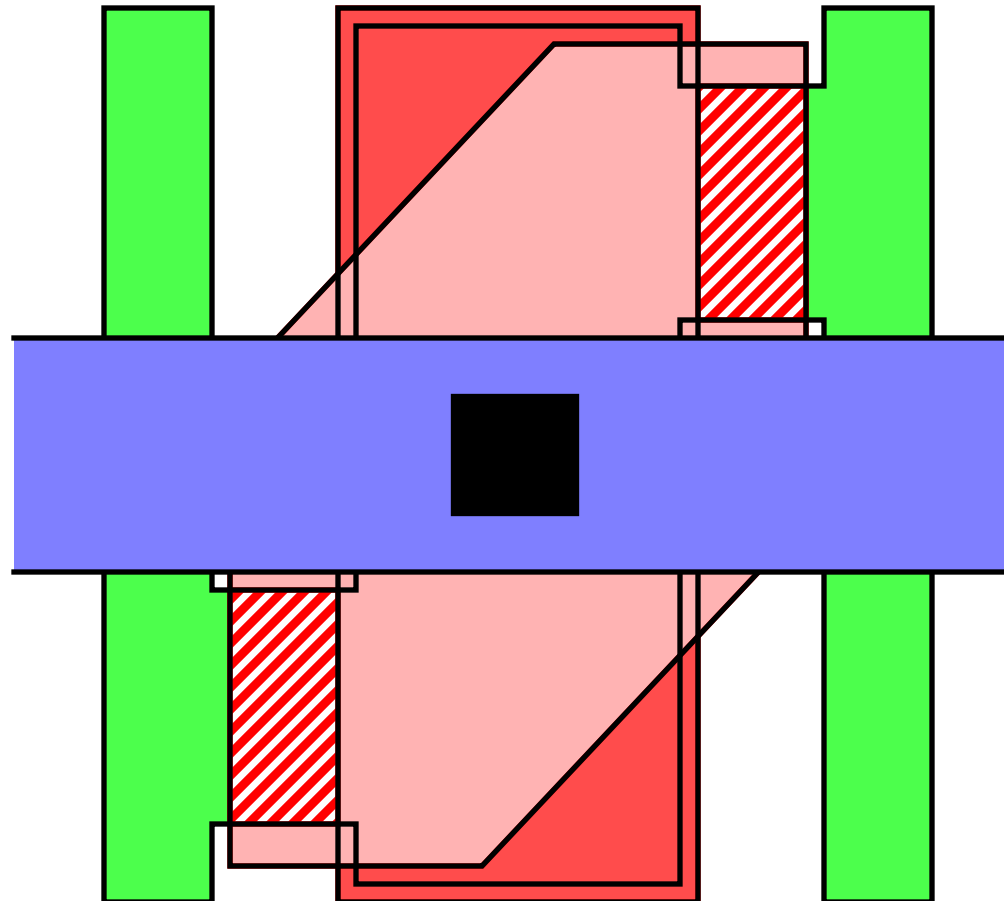
# eDRAM: 2-bit cell (CMU)



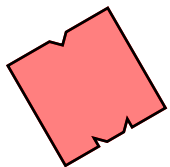
**Poly II**



# eDRAM: 2-bit cell (CMU)



Via & Metal 1





# eDRAM: 2-bit cell (CMU)

